

ABSTRACT OF THE DISCLOSURE

An exposure apparatus includes an illumination optical system for illuminating a reticle with illuminating light from a light source, a projection optical system for projecting a pattern, which has been formed on the reticle, onto a photosensitive substrate, a holding unit for holding the reticle, a reticle transport system for transporting the reticle, a substrate stage capable of holding and moving the substrate, and a substrate transport system for transporting the substrate. Further, at least one of a pair of the reticle transport system and the holding unit and a pair of the substrate transport system and the substrate stage is accommodated in a partitioned circulation space in which inert gas is filled and the inert gas is circulated by a circulating system having a temperature control mechanism.